

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	4	430/313.cor. and 430/328.cxr. and (etch\$3 with chamber)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 11:43
L2	7	250/504R-504H.ccls. and (neon or Ne) with (ultraviolet or uv) not 1	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 11:48
L3	19	430/328.ccls. and (uv or ultraviolet or ultra adj violet) same (temperature or \$4"degree") same plasma not 1 not 2	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 11:53
L4	237	430/328.ccls. and (uv or ultraviolet or ultra adj violet) same (temperature or \$4"degree") not 1 not 2 not 3	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 11:57
L5	46	430/313.ccls. and (uv or ultraviolet or ultra adj violet) same (\$4"degree") same plasma not 1 not 2 not 3 not 4	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 12:04
L6	41	250/504R-504H.ccls. and plasma and (uv or ultraviolet or ultra adj violet) same (\$4"degree") not 1 not 2 not 3 not 4 not 5	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 12:07
L7	454	(resist or photoresist) same (uv or ultraviolet or ultra adj violet) same (\$4"degree") same plasma not 1 not 2 not 3 not 4 not 5 not 6	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 12:13
L8	223	((ultraviolet or uv) with (Ne or neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist)) not 1 not 2 not 3 not 4 not 5 not 6 not 7	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 12:18
L9	429	((ultraviolet or uv) with (Ne or neon)) same (inert or Ar or argon) not 1 not 2 not 3 not 4 not 5 not 6 not 7 not 8	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 12:20
L10	0	((ultraviolet or uv) with (Ne or neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ne or neon) same (flow or flowrate)) not 1 not 2 not 3 not 4 not 5 not 6 not 7 not 8 not 9	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 12:24

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L11	10	((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and (Ne or neon) not 1 not 2 not 3 not 4 not 5 not 6 not 7 not 8 not 9	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 12:30
L12	0	((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and (Ne or neon) not 1 not 2 not 3 not 4 not 5 not 6 not 7 not 8 not 9 not 11	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 12:44
L13	0	((ultraviolet or uv) with (Ne or neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate)) not 1 not 2 not 3 not 4 not 5 not 6 not 7 not 8 not 9 not 11	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 12:45
L14	11	(430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)) not 1 not 2 not 3 not 4 not 5 not 6 not 7 not 8 not 9 not 11	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 12:47
L15	6	(430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) same (flow or flowrate or rate)) not 1 not 2 not 3 not 4 not 5 not 6 not 7 not 8 not 9 not 11 not 14	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 12:49
L16	0	((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not 1 not 2 not 3 not 4 not 5 not 6 not 7 not 8 not 9 not 11 not 14 not 15	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 12:50
L17	44	((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not 1 not 2 not 3 not 4 not 5 not 6 not 7 not 8 not 9 not 11 not 14 not 15	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 12:51

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L18	54	(((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((silicon or Si) near3 (wafer or substrate))) and etch\$3 not 1 not 2 not 3 not 4 not 5 not 6 not 7 not 8 not 9 not 11 not 14 not 15 not 17	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 13:01
L19	19	(((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and etch\$3 not 1 not 2 not 3 not 4 not 5 not 6 not 7 not 8 not 9 not 11 not 14 not 15 not 17 not 18	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 13:05
L20	13	430/313.cor. and 430/328.cxr. not 1 not 2 not 3 not 4 not 5 not 6 not 7 not 8 not 9 not 11 not 14 not 15 not 17 not 18 not 19	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 13:08
L21	145	((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not 1 not 2 not 3 not 4 not 5 not 6 not 7 not 8 not 9 not 11 not 14 not 15 not 17 not 18 not 19 not 20	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 13:13
L22	455	(430/328.ccls. not 430/313.cor.) not 1 not 2 not 3 not 4 not 5 not 6 not 7 not 8 not 9 not 11 not 14 not 15 not 17 not 18 not 19 not 20 not 21	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 13:19
L23	149	(Francis near2 Ko or Richard near2 Chen or Charlie near2 Lee).in. not 1 not 2 not 3 not 4 not 5 not 6 not 7 not 8 not 9 not 11 not 14 not 15 not 17 not 18 not 19 not 20 not 21 not 22	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2006/08/10 13:34
L25	1	((method or process) and ((bilayer or bi adj layer or dual or second or top) near2 (resist or photoresist)) and (ultraviolet or ultra adj violet or UV) near5 (cross adj link\$3 or cur\$3 or harden\$3) near5 (((organosilicon or silicon or "Si") near2 contain\$3) or silyl\$5) near5 (polymer\$7 or photopolymer\$7 or resist or photoresist) and (expos\$3 or radiat\$3 or irradiat\$3) and develop\$4 and etch\$3 and selectiv\$3).clm.	US-PGPUB; USPAT	ADJ	ON	2006/08/10 14:06

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L26	2	((method or process) and ((bilayer or bi adj layer or dual or second or top) near2 (resist or photoresist)) and (ultraviolet or ultra adj violet or UV) and (cross adj link\$3 or cur\$3 or harden\$3) and (((organosilicon or silicon or "Si") near2 contain\$3) or silyl\$5) and (polymer\$7 or photopolymer\$7 or resist or photoresist) and (expos\$3 or radiat\$3 or irradiat\$3) and develop\$4 and etch\$3 and selectiv\$3).clm.	US-PGPUB; USPAT	ADJ	ON	2006/08/10 14:11
L27	5	((method or process) and ((bilayer or bi adj layer or dual or second or top) near2 (resist or photoresist)) and (ultraviolet or ultra adj violet or UV) and (cross adj link\$3 or cur\$3 or harden\$3) and (((organosilicon or silicon or "Si") near2 contain\$3) or silyl\$5) and (polymer\$7 or photopolymer\$7 or resist or photoresist) and (expos\$3 or radiat\$3 or irradiat\$3) and develop\$4 and etch\$3).clm. not 26	US-PGPUB; USPAT	ADJ	ON	2006/08/10 14:12